

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S110	1610	(ald or ale or atomic near2 layer near2 (deposit \$5 or epitax\$4) or sequential near2 (Ovd or vapor near2 deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj (oxide or dioxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:03
S111	264	(ald or ale or atomic near2 layer near2 (deposit \$5 or epitax\$4) or sequential near2 (Ovd or vapor near2 deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj (oxide or dioxide)) and (silicon or si) near10 organic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:04
S112	7	(ald or ale or atomic near2 layer near2 (deposit \$5 or epitax\$4) or sequential near2 (Ovd or vapor near2 deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj (oxide or dioxide)) and (silicon or si) near10 organic and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:05
S113	2	(ald or ale or atomic near2 layer near2 (deposit \$5 or epitax\$4) or sequential near2 (Ovd or vapor near2 deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj (oxide or dioxide)) and (silane) near10 organic and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:28
S114	5	(ald or ale or atomic near2 layer near2 (deposit \$5 or epitax\$4) or sequential near2 (Ovd or vapor near2 deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj (oxide or dioxide)) and (silane or si or silicon) near10 ligand and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:35

S115	2770	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (silane or si or silicon) near10 (ligand or organic) and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:36
S116	8	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (silane or si or silicon) near10 (ligand or organic) and @py<"2003" and (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:37
S117	3	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (silane or si or silicon) near10 (amino) and @py<"2003" and (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:39
S118	64	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and organic near2 precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:44
S119	47	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and organic near2 ligand	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 09:48
S122	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and TDMAS and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 10:58
S121	44	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and TDMAS	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 10:58

S120	15	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and amino near4 silane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 10:58
S123	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near10 (ale or ald or atomic near2 layer near2 (epitax\$5 or deposit\$5)) and trisdimethylaminosilane and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:00
S125	8	Morishita near10 Silicon adj Dioxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:09
S124	8294769	Morishita, et "al." New Substances for Atomic-Layer Deposition of Silicon Dioxide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:09
S127	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMAS! dimethylaminosilane or dimethyl \$1aminosilane) and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:20
S126	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMAS!) and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:20
S129	12	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMAS! dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:21

S128	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) near15 (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and @py<"2003"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:21
S133	5	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and (ald or ale or atomic near2 layer near2 (epitax\$4 or deposit \$5) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:35
S132	0	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and (ald or ale or atomic near2 layer near2 (epitax\$4 or deposit \$5) and @py<"2001"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:35
S131	126	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and (ald or ale or atomic near2 layer near2 (epitax\$4 or deposit \$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:35
S130	267	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:35
S134	18	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:40

S136	18	S135 and S134	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:51
S135	26	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) or silica) and (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:51
S138	887	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASi \$5dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or \$7amino \$1silane) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:53
S137	23	(sio or "sio.sub.2" or silicon adj (oxide or dioxide) and (trisdimethylaminosilane TDMASi \$5dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" ) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:53
S141	31	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMASi \$5dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or \$7amino\$1silane) and @py<"2004" and (cvd or vapor near2 deposit\$5 or epitax\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:54
S140	1	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMASi \$5dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or \$7amino\$1silane) and @py<"2004" and (ald or ale or atomic near2 layer near2 (epitax\$4 or deposit\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:54

S139	73	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) near15 (trisdimethylaminosilane TDMASI \$5dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or \$7amino\$1silane) and @py<"2004"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 11:54
S143	30	S142 not S141	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:09
S142	61	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) same (trisdimethylaminosilane TDMASI \$5dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or \$7amino\$1silane) and @py<"2004" and (cvd or vapor near2 deposit\$5 or epitax\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:09
S144	111	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) same (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" )	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:16
S145	111	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) same (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SiH(N(CH.sub.3).sub.2).sub.3")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:17
S147	12	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) and (trisdimethylaminosilane TDMASI dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SiH(N(CH.sub.3).sub.2).sub.3") and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:18

S146	0	(sio or "sio.sub.2" or silicon adj (oxide or dioxide)) same (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl\$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3") and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:18
S149	15	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:19
S148	0	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3") and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:19
S152	29	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3" or AMINOSILANE or amino\$1silane or \$6aminosilane or \$6amino\$1silane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:20
S151	24	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3" or AMINO\$1SILANE)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:20
S150	26	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (trisdimethylaminosilane TDMASi dimethylaminosilane or dimethyl \$1aminosilane or "HS[N(CH.sub.3).sub.2 ].sub.3" or "SH(N(CH.sub.3).sub.2).sub.3" or AMINOSILANE)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:20

S153	1590	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj oxide or silicon adj dioxide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:22
S157	4	S156 and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:23
S156	379	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj oxide or silicon adj dioxide) and (aminosilane or silicon near5 precursor or si near2 precursor or amino near5 silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:23
S155	371	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj oxide or silicon adj dioxide) and (aminosilane or silicon near5 precursor or si near2 precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:23
S154	597	(ald or ale or atomic near2 layer near2 (epitax\$5 or deposit\$5)) near15 (sio or "sio.sub.2" or silicon adj oxide or silicon adj dioxide) and (silane or silicon near5 precursor or si near2 precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/11 14:23
S158	4	("4058430"   "4861417"   "5166092"   "5256244").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/11 14:27
S159	2	S158 and (silicon or "sio.sub.2" or sio)	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/11 14:28
S161	39	reactor near2 ald near10 asm	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:41
S160	83	ald near10 asm	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:41



S164	6	reactor near2 ald near10 asm and @py<"2004"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:42
S163	0	reactor near2 ald near10 asm and @py<"2002"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:42
S162	0	reactor near2 ald near10 asm and @py<"2001"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:42
S165	1	"6342277".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:43
S166	1	"5916365".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:46
S168	13	(silicon near2 dioxide or "sio.sub.2") same (atom \$3 near2 layer or monolayer or mono\$1layer) same (TEOS or tetraethyloxysilane) and @py<"2004"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:53
S167	91	(silicon near2 dioxide or "sio.sub.2") same (atom \$3 near2 layer or monolayer or mono\$1layer) same (TEOS or tetraethyloxysilane)	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:53
S169	13	(silicon near2 dioxide or "sio.sub.2") same (atom \$3 near2 layer or monolayer or mono\$1layer) same (TEOS or tetraethyloxysilane tetraethosiloxane) and @py<"2004"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:54
S170	17	(silicon near2 dioxide or "sio.sub.2") same (atom \$3 near2 layer or monolayer or mono\$1layer) same (amino near2 silane or aminosilane or \$7aminosilane) and @py<"2004"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:55
S171	14	(silicon near2 dioxide or "sio.sub.2") same (atom \$3 near2 layer or monolayer or mono\$1layer) same (organo near2 silane or organic near2 silane) and @py<"2004"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 10:57
S172	1	"5916365".pn. and silicon adj dioxide	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 11:05
S174	1	"5916365".pn. and "o.sub.3"	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 11:08

S173	0	"5916365".pn. and ozone	US-PGPUB; USPAT; USOCR	OR	ON	2009/06/12 11:08
S175	183	sequential near2 cvd	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:10
S178	10	sequential near2 cvd and ("sio.sub.2" or silicon adj dioxide) same (atom\$4 near2 layer or monolayer or mono\$1layer) and @py<"2004"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:11
S177	80	sequential near2 cvd and ("sio.sub.2" or silicon adj dioxide) and @py<"2004"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:11
S176	120	sequential near2 cvd and ("sio.sub.2" or silicon adj dioxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:11
S181	60	(cvd or vapor near2 deposit\$5 or vapor near2 epitax\$5) same ("sio.sub.2" or silicon adj dioxide) near15 (atom\$4 near2 layer or monolayer or mono\$1layer) and @py<"2004"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:13

S180	393	(cvd or vapor near2 deposit\$5 or vapor near2 epitax\$5) and ("sio.sub.2" or silicon adj dioxide) near15 (atom\$4 near2 layer or monolayer or mono\$1layer) and @py<"2004"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:13
S179	925	(cvd or vapor near2 deposit\$5 or vapor near2 epitax\$5) and ("sio.sub.2" or silicon adj dioxide) same (atom\$4 near2 layer or monolayer or mono\$1layer) and @py<"2004"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:13
S182	2	"5917571".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/12 11:48
S184	3	amino near2 silane near15 (ald or ale or alcvd or al\$1cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/20 11:37
S183	0	APDMES near15 (ald or ale or alcvd or al\$1cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/20 11:37
S185	16	(TDMAS) near15 (ald or ale or alcvd or al\$1cvd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/20 11:38

S186	2	"6352593".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/20 11:44
S187	86	ieskela near4 ald	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/20 16:35
S188	311	(apdmes or aminopropyldimethylethoxysilane)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 08:50
S189	6	(apdmes or aminopropyldimethylethoxysilane) near15 (sio or silicon near2 oxide or silicon near2 dioxide or sio2 or "sio.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 08:51
S190	2	"5917571".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:00
S191	2	"6861334".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:29
S192	112	atomic near2 layer near2 growth near10 (sio or sio2 or "sio.sub.2" or silicon near2 (dioxide or oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:39

S194	67	atomic near2 layer near2 growth near10 (sio or sio2 or "sio.sub.2" or silicon near2 (dioxide or oxide)) and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:40
S193	10	atomic near2 layer near2 growth near10 (sio or sio2 or "sio.sub.2" or silicon near2 (dioxide or oxide)) and amino near2 silane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:40
S195	13	atomic near2 layer near2 growth near10 (sio or sio2 or "sio.sub.2" or silicon near2 (dioxide or oxide)) and @py<"2002"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 09:41
S196	4	"03082769"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 10:19
S197	2	"5917571".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 14:05
S198	10	US-5496582-\$.D.ID. OR US-5972430-\$.D.ID. OR US-6537613-\$.D.ID. OR US-6849305-\$.D.ID. OR US-7045430-\$.D.ID.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 16:00
S199	2	"20060228888"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 16:02

S200	104	(eva near2 tois or suvi near2 haukka or marko near2 tuominen).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2009/06/21 22:59
------	-----	---	---	----	----	---------------------

6/22/09 12:34:04 PM

H:\EAST\10148525.wsp